

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	118	(photoresist or photopolymer or (polymer adj layer)) same (develop or developing or development or developer) same (sufficient adj5 time)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/08 11:41
S1	8	(photoresist or photopolymer or (polymer adj layer)) same (develop or developing or development) same (wet or wetting or stay or staying or remain or remaining or dwell or dwelling) same (wash or washing or rinse or rinsing) same (sudden adj2 change adj3 pH)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/08 09:04
S2	657	(photoresist or photopolymer or (polymer adj layer)) same (develop or developing or development) same (wet or wetting or stay or staying or remain or remaining or dwell or dwelling) same (wash or washing or rinse or rinsing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/08 11:39
S3	0	(photoresist or photopolymer or (polymer adj layer)) same ((addition or additional or additionally) adj2 (develop or developing or development)) same (wet or wetting or stay or staying or remain or remaining or dwell or dwelling) same (wash or washing or rinse or rinsing) same (sudden adj2 change adj3 pH)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/08 08:59
S4	0	(photoresist or photopolymer or (polymer adj layer)) same ((addition or additional or additionally) adj2 (develop or developing or development)) same (wet or wetting or stay or staying or remain or remaining or dwell or dwelling) same (wash or washing or rinse or rinsing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/08 08:58
S5	6	(photoresist or photopolymer or (polymer adj layer)) same ((addition or additional or additionally) adj5 (develop or developing or development or developer)) same (wet or wetting or stay or staying or remain or remaining or dwell or dwelling) same (wash or washing or rinse or rinsing) same (sudden adj2 change adj3 pH)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/08 09:02

S6	8	(photoresist or photopolymer or (polymer adj layer)) same ((addition or additional or additionally) adj5 (develop or developing or development or developer)) same (wet or wetting or stay or staying or remain or remaining or dwell or dwelling) same (wash or washing or rinse or rinsing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/08 09:06
S7	8	(photoresist or photopolymer or (polymer adj layer)) same (develop or developing or development) same (sudden adj2 change adj3 pH)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/08 09:05
S8	34	(photoresist or photopolymer or (polymer adj layer)) same ((addition or additional or additionally) adj5 (develop or developing or development or developer)) same (wash or washing or rinse or rinsing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/08 09:06